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LI(10) **Pub. No.: US 2017/0168347 A1**(43) **Pub. Date: Jun. 15, 2017**(54) **LIQUID CRYSTAL DISPLAY PANEL AND
ARRAY SUBSTRATE OF THE SAME**(71) Applicants: **Shenzhen China Star Optoelectronics
Technology Co., Ltd.**, Shenzhen,
Guangdong (CN); **Wuhan China Star
Optoelectronics Technology Co., Ltd.**,
Wuhan, Hubei (CN)(72) Inventor: **Yafeng LI**, Shenzhen, Guangdong (CN)(73) Assignees: **Shenzhen China Star Optoelectronics
Technology Co., Ltd.**, Shenzhen,
Guangdong (CN); **WUHAN CHINA
STAR OPTOELECTRONICS
TECHNOLOGY CO., LTD.**, Wuhan,
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(57)

ABSTRACT

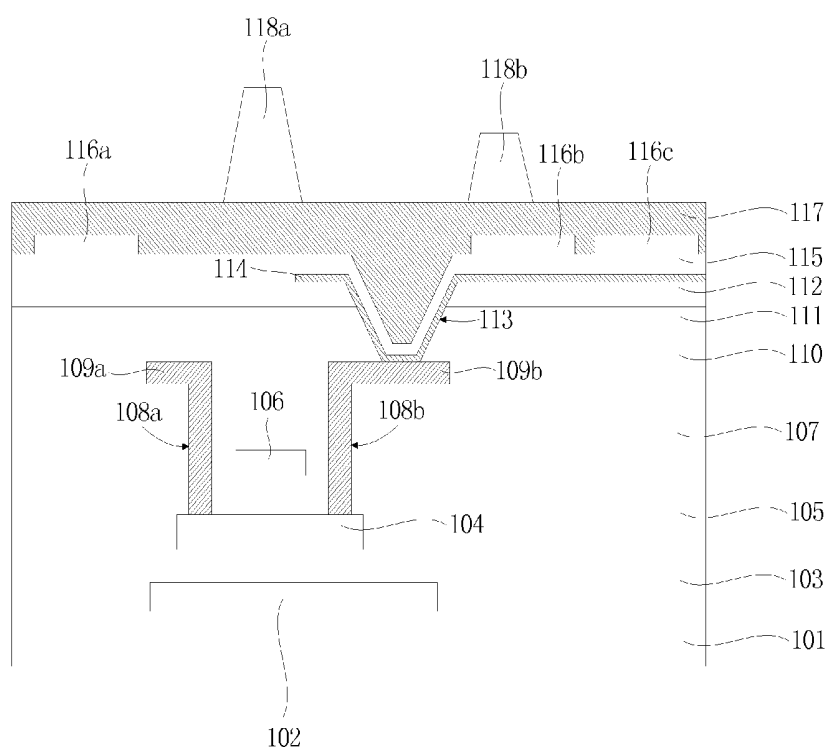
An array substrate for a liquid crystal display panel is disclosed. The array substrate includes a first substrate, a Lower Temperature Polycrystal Silicon (LTPS) Thin-Film-Transistor (TFT) disposed on the first substrate, a color photoresist layer disposed on the LTPS TFT, and multiple photo spacers disposed above the color photoresist layer. A liquid crystal display panel including the array substrate and a second substrate disposed oppositely to the array substrate is also disclosed. The present invention utilizes the second substrate to be aligned with the LTPS TFT array substrate in order to form the liquid crystal display panel. Because the second substrate is a bare substrate (without a pattern), when the second substrate is aligned with the array substrate, the alignment precision is not under consideration. Accordingly, apertures ratios of the liquid crystal display panel do not have difference.

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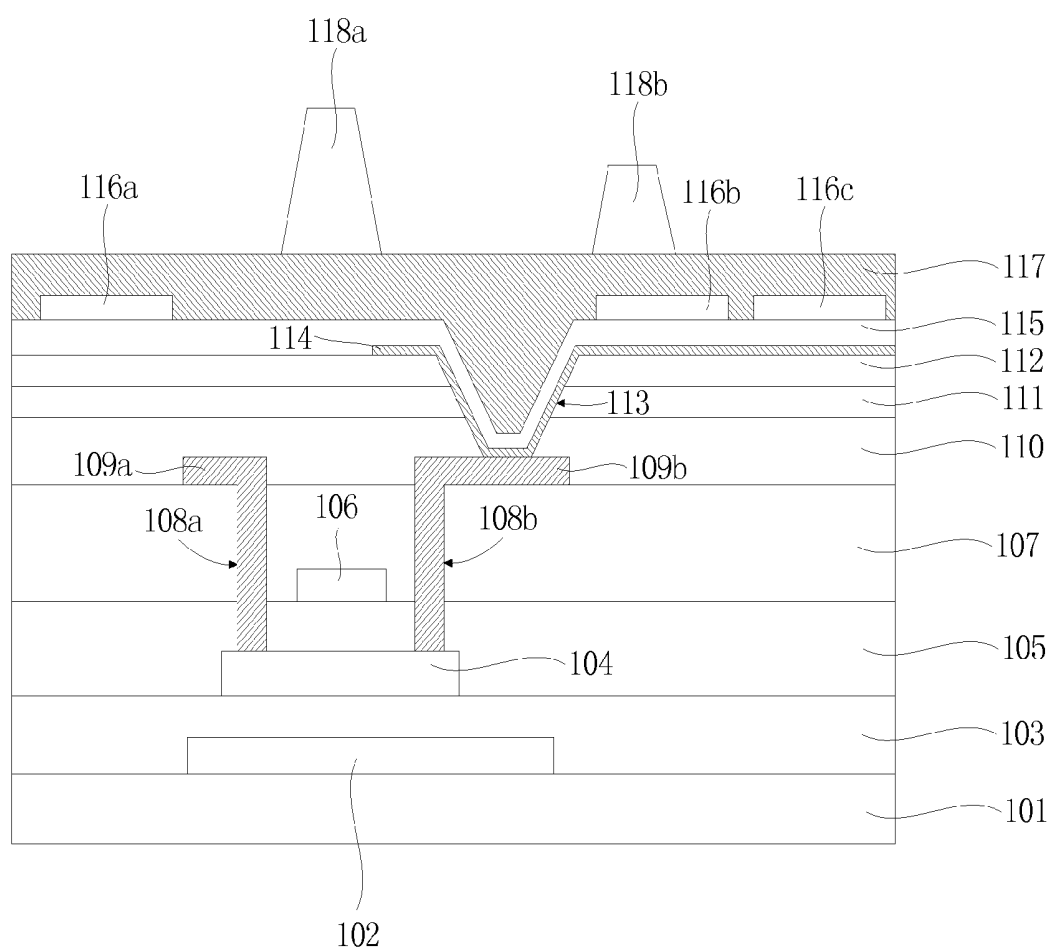


FIG. 1

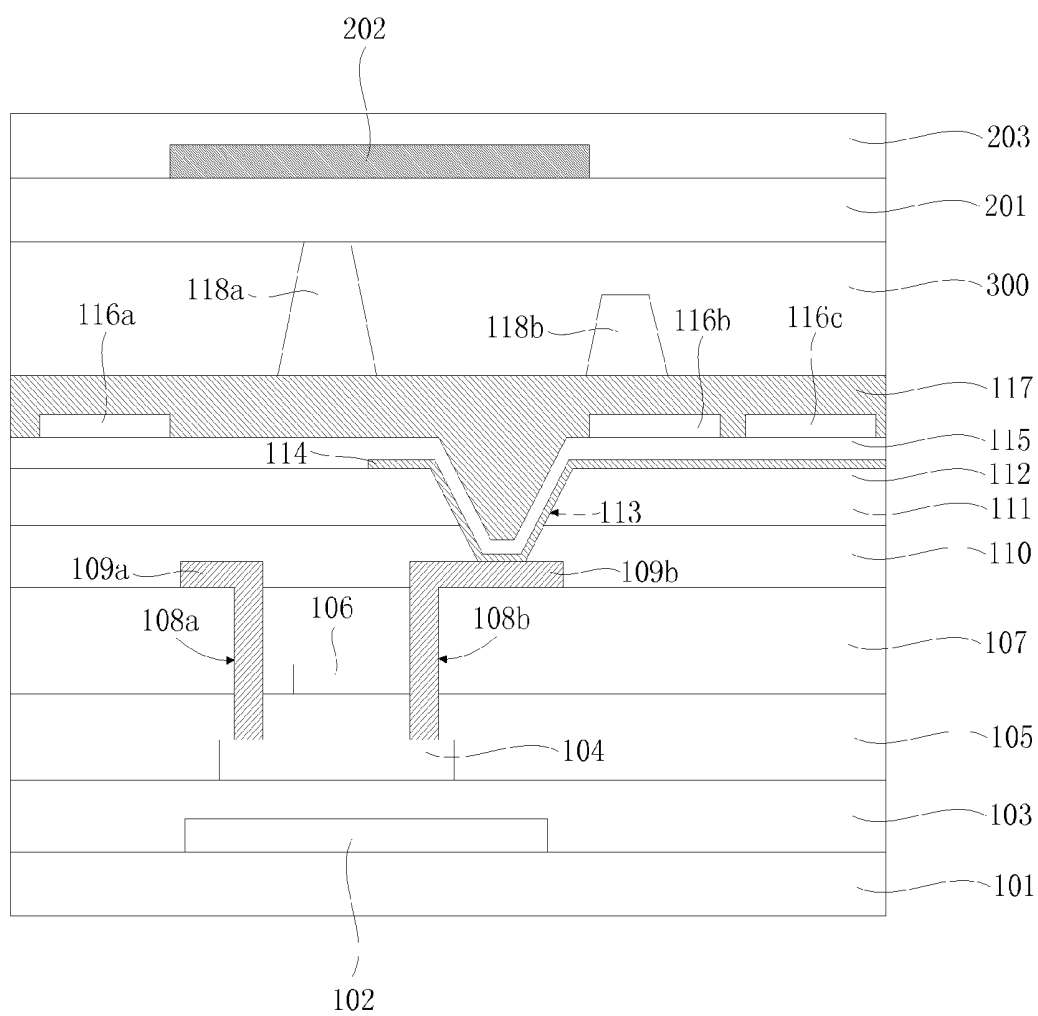


FIG. 2

LIQUID CRYSTAL DISPLAY PANEL AND ARRAY SUBSTRATE OF THE SAME

BACKGROUND OF THE INVENTION

[0001] 1. Field of the Invention

[0002] The present invention belongs to a liquid crystal display technology field, and more particular to a Lower-Temperature-Polycrystal-Silicon (LTPS) Thin-Film-Transistor (TFT) array substrate and a liquid crystal display panel having the same.

[0003] 2. Description of Related Art

[0004] With the development of optical and semiconductor technology, the Flat Panel Display (FPD) also develops vigorously. In many types of the Flat Panel Display, the Liquid Crystal Display (LCD) has become the mainstream of the market because of superior characteristics of high space utilization efficiency, low power consumption and low electromagnetic interference.

[0005] Currently, an amorphous silicon thin film transistor (a-Si TFT) is widely used as a switching element of the LCD. However, a a-Si TFT LCD is limited for satisfying the requirements of thin, lightweight, high-definition, high brightness, high reliability, low power consumption. Comparing with the a-Si TFT LCD, a Lower-Temperature-Polycrystal-Silicon (LTPS) TFT LCD has an obvious advantage for satisfying the above requirements.

[0006] In a current LTPS-TFT LCD, a liquid crystal display panel formed by a color-filter substrate (referred to as CF substrate) and an array substrate aligned with each other is usually provided. In the liquid crystal display panel, in order to prevent an edge of a pixel from light leakage, a black matrix (referred to as BM) on the CF substrate is usually utilized to shield an edge of a pixel. At the same time, when a light enters from a side of the CF substrate, the black matrix can also prevent a decreasing contrast ratio problem because of a reflective light of a source/drain metal layer on the array substrate. Accordingly, when the CF substrate and the array substrate are aligned, an alignment precision of the black matrix and the source/drain metal layer should be considered. Under the current process capability, an alignment deviation of the black matrix and the source/drain metal layer will be generated. Sometimes, the alignment deviation reaches $\pm 5 \mu\text{m}$ such that apertures ratio for pixels of the liquid crystal display panel manufactured by the current process capability exist great difference in order to affect a quality of a liquid crystal display panel.

SUMMARY OF THE INVENTION

[0007] In order to solve the above technology problems, the purpose of the present invention is to provide an array substrate for a liquid crystal display panel, comprising: a first substrate; a Lower-Temperature-Polycrystal-Silicon (LTPS) Thin-Film-Transistor (TFT) disposed on the first substrate; a color photoresist layer disposed on the LTPS TFT; and multiple photo spacers disposed above the color photoresist layer.

[0008] Wherein, the array substrate further includes: a light-shielding layer disposed between the first substrate and the LTPS TFT, wherein, the light-shielding layer and the LTPS TFT are disposed oppositely.

[0009] Wherein, the array substrate further includes: a first insulation layer disposed between the light-shielding layer and the LTPS TFT, wherein, the first insulation layer covers the light-shielding layer.

[0010] Wherein, the LTPS TFT includes: a polysilicon layer disposed on the first insulation layer; a second insulation layer disposed on the first insulation layer and covering the polysilicon layer; a gate metal layer disposed on the second insulation layer; a third insulation layer disposed on the second insulation layer covering on the gate metal layer; a first through hole and a second through hole located in the third insulation layer and the second insulation layer, wherein, the first through hole and the second through hole reveal a surface of the polysilicon layer; a source metal layer and a drain metal layer disposed on the third insulation layer, wherein, the source metal layer fills the first through hole and contacts with the surface of the polysilicon layer, and the drain metal layer fills the second through hole and contacts with the surface of the polysilicon layer; a first planar layer disposed on the third insulation layer and covering the source metal layer and the drain metal layer; a common electrode layer disposed on the first planar layer; a first passivation layer disposed on the common electrode layer; a via hole located in the first passivation layer, the common electrode layer and the first planar layer, wherein, the via hole reveals a surface of the drain metal layer; a pixel electrode layer disposed on the first passivation layer, wherein, the pixel electrode layer is contacted with the surface of the drain metal layer by the via hole; and a second passivation layer covering the pixel electrode layer.

[0011] Wherein, the color photoresist layer includes: a red photoresist layer, a green photoresist layer and a blue photoresist layer, wherein, the red photoresist layer, the green photoresist layer and the blue photoresist layer are formed on the second passivation layer.

[0012] Wherein, the array substrate further includes: a second planar layer disposed on the second passivation layer, wherein, the second planar layer fills the via hole.

[0013] Wherein, the multiple photo spacers includes: a main photo spacer and a sub photo spacer, wherein, the main photo spacer and the sub photo spacer are both located on the second planar layer.

[0014] Another purpose of the present invention is to provide a liquid crystal display panel comprising a second substrate disposed oppositely to the above array substrate.

[0015] Wherein, the liquid crystal display panel further includes: a black light-shielding layer disposed at a surface of the second substrate far away from the array substrate, wherein, the black light-shielding layer is disposed oppositely to the LTPS TFT, and a light-shielding area of the black light-shielding layer is greater than a light-shielding area of the light-shielding layer of the array substrate.

[0016] Wherein, the liquid crystal display panel further includes: a third passivation layer disposed at a surface of the second substrate far away from the array substrate and covering the black light-shielding layer.

[0017] The beneficial effects of the present invention: because the second substrate is a bare substrate (without any pattern), when the second substrate is aligned with the array substrate, the alignment precision is not under consideration. Accordingly, apertures ratios of the liquid crystal display panel do not have difference.

BRIEF DESCRIPTION OF THE DRAWINGS

[0018] FIG. 1 is a schematic diagram of a LTPS-TFT array substrate according to an embodiment of the present invention; and

[0019] FIG. 2 is a schematic diagram of a liquid crystal display panel according to an embodiment of the present invention.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENT

[0020] The following content combines with the drawings and the embodiment for describing the present invention in detail. It is obvious that the following embodiments are only some embodiments of the present invention. For the person of ordinary skill in the art without creative effort, the other embodiments obtained thereby are still covered by the present invention.

[0021] It should be noted that, herein, relational terms such as first and second, and the like are only used to distinguish one entity or operation from another entity or operation. It is not required or implied that these entities or operations exist any such relationship or order between them. Moreover, the terms “comprise,” “include,” or any other variation thereof, are intended to cover a non-exclusive inclusion, such that a series of elements including the process, method, article or device that includes not only those elements but also other elements not expressly listed or further comprising such process, method, article or device inherent elements. Without more constraints, by the statement “comprises one” element defined does not exclude the existence of additional identical elements in the process, method, article, or apparatus.

[0022] It can also be understood that when a layer or an element is called or formed on another layer or a substrate, the layer or the element can be directly formed on the another layer or the substrate, or an intermediate layer may exist.

[0023] FIG. 1 is a schematic diagram of a LTPS-TFT array substrate according to an embodiment of the present invention

[0024] With reference to FIG. 1, a LTPS-TFT array substrate according to an embodiment of the present invention includes: a first substrate 101, a Lower Temperature-Polycrystal-Silicon (LTPS) Thin-Film-Transistor (TFT), a color photoresist layer formed on the LTPS TFT, and multiple photo spacers formed above the color photoresist layer 116a, 116b, and 116c. In the present embodiment, the first substrate 101 can be a transparent glass substrate, but the present invention is not limited. For example, the first substrate 101 can also be a transparent resin substrate.

[0025] Furthermore, in order to prevent the LTPS TFT from generating a leakage current because of irradiating by a light, the array substrate also includes: a light-shielding layer 102 formed between the first substrate 101 and the LTPS TFT. Wherein, the light-shielding layer 102 and the LTPS TFT are disposed oppositely so that the light-shielding layer 102 shields a light for a channel of the LTPS TFT. Furthermore, the light-shielding layer 102 is disposed right oppositely to the LTPS TFT. That is, viewing from bottom to top, the light-shielding layer 102 can completely shield the LTPS TFT.

[0026] Besides, the array substrate further includes: a first insulation layer 103 formed between the first substrate 101

and the LTPS TFT. Wherein, the first insulation layer 103 covers the light-shielding layer 102. That is, the light-shielding layer 102 is directly formed on the first substrate 101. The first insulation layer 103 is directly formed on the first substrate 101 and covers the light-shielding layer 102. The LTPS TFT is directly formed on the first insulation layer 103. In the present embodiment, the first insulation layer 103 is formed by silicon nitride and silicon oxide. However, the present invention is not limited.

[0027] The following content will describe the LTPS TFT according to an embodiment of the present invention in detail. The LTPS TFT according to an embodiment of the present invention includes:

[0028] A polysilicon layer 104 is provided on the first insulation layer 103, the polysilicon layer 104 is used for forming a carrier moving channel;

[0029] A second insulation layer 105 is disposed on the first insulation layer 103 and covers the polysilicon layer 104. Wherein, in the present embodiment, the second insulation layer 105 is formed by silicon nitride and silicon oxide. However, the present invention is not limited.

[0030] A gate metal layer 106 is disposed on the second insulation layer 105.

[0031] A third insulation layer 107 is disposed on the second insulation layer 105 and covers the gate metal layer 106. Wherein, in the present embodiment, the third insulation layer 107 is formed by silicon nitride and silicon oxide. However, the present invention is not limited.

[0032] A first through hole 108a and a second through hole 108b are located in the third insulation layer 107 and the second insulation layer 105. Wherein, the first through hole 108a and the second through hole 108b reveal a surface of the polysilicon layer 104.

[0033] A source metal layer 109a and a drain metal layer 109b are disposed on the third insulation layer 107. Wherein, the source metal layer 109a fills the first through hole 108a and contacts with the surface of the polysilicon layer 104. The drain metal layer 109b fills the second through hole 108b and contacts with the surface of the polysilicon layer 104.

[0034] A first planar layer 110 disposed on the third insulation layer 107 and covers the source metal layer 109a and the drain metal layer 109b. In the present embodiment, the first planar layer 110 is an organic planar layer. However, the present invention is not limited.

[0035] A common electrode layer 111 disposed on the first planar layer 110. In the present embodiment, the common electrode layer 111 is made of Indium-Tin-Oxide (ITO). However, the present invention is not limited.

[0036] A first passivation layer 112 disposed on the common electrode layer 111.

[0037] A via hole 113 located in the first passivation layer 112, the common electrode layer 111 and the first planar layer 110. Wherein, the via hole 113 reveals a surface of the drain metal layer 109b.

[0038] A pixel electrode layer 114 is disposed on the first passivation layer 112. Wherein, the pixel electrode layer 114 is contacted with the surface of the drain metal layer 109b by the via hole 113. In the present embodiment, the pixel electrode layer 114 is made of Indium-Tin-Oxide (ITO). However, the present invention is not limited.

[0039] A second passivation layer 115 covers the pixel electrode layer 114.

[0040] In addition, in the present embodiment, the color photoresist layer includes: a red photoresist layer **116a**, a green photoresist layer **116b** and a blue photoresist layer **116c**. Wherein, the red photoresist layer **116a**, the green photoresist layer **116b** and the blue photoresist layer **116c** are directly formed on the second passivation layer **115**.

[0041] Besides, the array substrate also includes: a second planar layer **117** is disposed on the second passivation layer **115** and covers the red photoresist layer **116a**, the green photoresist layer **116b** and the blue photoresist layer **116c**. Wherein, the second planar layer **117** fills the via hole **113**. In the present embodiment, the second planar layer **117** is an organic planar layer. However, the present invention is not limited.

[0042] Furthermore, the photo spacers include: a main photo spacer **118a** and a sub photo spacer **118b**. Wherein, the main photo spacer **118a** and the sub photo spacer **118b** are both located on the second planar layer **117**.

[0043] FIG. 2 is a schematic diagram of a liquid crystal display panel according to an embodiment of the present invention.

[0044] With reference to FIG. 2, the liquid crystal display panel according to an embodiment of the present invention includes: a second substrate **201** disposed oppositely to the LTPS TFT array substrate, and a liquid crystal layer **300** disposed between the array substrate and the second substrate **201**.

[0045] In the present embodiment, the second substrate **201** can be a transparent glass substrate, but the present invention is not limited. For example, the second substrate **201** can also be a transparent resin substrate.

[0046] In order to prevent an incident light from the second substrate **201** from being reflected by the metal layers (such as the source metal layer **109a** and the drain metal layer **109b**) of the LTPS TFT array substrate so as to decrease the contrast ratio of the liquid crystal display panel, in the present embodiment, a surface of the second substrate **201** far away from the LTPS TFT array substrate (that is, a top surface of the second substrate **201**) is provided with a black light-shielding layer **202**. The black light-shielding layer **202** is disposed oppositely to the LTPS TFT. Furthermore, the black light-shielding layer **202** is disposed right opposite to the LTPS TFT.

[0047] In addition, a light-shielding area of the black light-shielding layer **202** is greater than a light-shielding area of the light-shielding layer **102**. That is, when viewing from top to bottom, the black light-shielding layer **202** can completely block the LTPS TFT and the light-shielding layer **102**. In the present embodiment, the black light-shielding layer **202** is made of chromium. However, the present invention is not limited. For example, the black light-shielding layer **202** can be made by other black metals, or a black resin.

[0048] In addition, in order to protect the black light-shielding layer **202**, a third passivation layer **203** is disposed at a surface of the second substrate **201** far away from the LTPS TFT array substrate (that is, a top surface of the second substrate **201**). Wherein, the third passivation layer **203** covers the black light-shielding layer **202**.

[0049] In summary, according to the embodiments of the present invention, because the second substrate is a bare substrate (without a pattern), when the second substrate is aligned with the array substrate, the alignment precision is

not under consideration. Accordingly, apertures ratios of the liquid crystal display panel do not have difference.

[0050] The above embodiments of the present invention are not used to limit the claims of this invention. Any use of the content in the specification or in the drawings of the present invention which produces equivalent structures or equivalent processes, or directly or indirectly used in other related technical fields is still covered by the claims in the present invention.

What is claimed is:

1. An array substrate for a liquid crystal display panel, comprising:

a first substrate;

a Lower-Temperature-Polycrystal-Silicon (LTPS) Thin-Film-Transistor (TFT) disposed on the first substrate; a color photoresist layer disposed on the LTPS TFT; and multiple photo spacers disposed above the color photoresist layer.

2. The array substrate according to claim 1, wherein, the array substrate further includes: a light-shielding layer disposed between the first substrate and the LTPS TFT; wherein, the light-shielding layer and the LTPS TFT are disposed oppositely.

3. The array substrate according to claim 2, wherein, the array substrate further includes: a first insulation layer disposed between the light-shielding layer and the LTPS TFT, wherein, the first insulation layer covers the light-shielding layer.

4. The array substrate according to claim 3, wherein, the LTPS TFT includes:

a polysilicon layer disposed on the first insulation layer; a second insulation layer disposed on the first insulation layer and covering the polysilicon layer;

a gate metal layer disposed on the second insulation layer;

a third insulation layer disposed on the second insulation layer covering on the gate metal layer;

a first through hole and a second through hole located in the third insulation layer and the second insulation layer, wherein, the first through hole and the second through hole reveal a surface of the polysilicon layer;

a source metal layer and a drain metal layer disposed on the third insulation layer, wherein, the source metal layer fills the first through hole and contacts with the surface of the polysilicon layer, and the drain metal layer fills the second through hole and contacts with the surface of the polysilicon layer;

a first planar layer disposed on the third insulation layer and covering the source metal layer and the drain metal layer;

a common electrode layer disposed on the first planar layer;

a first passivation layer disposed on the common electrode layer;

a via hole located in the first passivation layer, the common electrode layer and the first planar layer, wherein, the via hole reveals a surface of the drain metal layer;

a pixel electrode layer disposed on the first passivation layer, wherein, the pixel electrode layer is contacted with the surface of the drain metal layer by the via hole; and

a second passivation layer covering the pixel electrode layer.

5. The array substrate according to claim 4, wherein, the color photoresist layer includes: a red photoresist layer, a green photoresist layer and a blue photoresist layer, wherein, the red photoresist layer, the green photoresist layer and the blue photoresist layer are formed on the second passivation layer.

6. The array substrate according to claim 5, wherein, the array substrate further includes: a second planar layer disposed on the color photoresist layer, wherein, the second planar layer fills the via hole.

7. The array substrate according to claim 6, wherein, the multiple photo spacers includes: multiple main photo spacers and multiple sub photo spacers, wherein, the multiple main photo spacers and the multiple sub photo spacers are all located on the second planar layer.

8. A liquid crystal display panel, comprising:

an array substrate; and

a second substrate disposed oppositely to the array substrate;

wherein, the array substrate includes:

a first substrate;

a Lower-Temperature-Polycrystal-Silicon (LTPS) Thin-Film-Transistor (TFT) disposed on the first substrate;

a color photoresist layer disposed on the LTPS TFT; and

multiple photo spacers disposed above the color photoresist layer.

9. The liquid crystal display panel according to claim 8, wherein, the array substrate further includes: a light-shielding layer disposed between the first substrate and the LTPS TFT, wherein, the light-shielding layer and the LTPS TFT are disposed oppositely.

10. The liquid crystal display panel according to claim 9, wherein, the array substrate further includes: a first insulation layer disposed between the light-shielding layer and the LTPS TFT, wherein, the first insulation layer covers the light-shielding layer.

11. The liquid crystal display panel according to claim 10, wherein, the LTPS TFT includes:

a polysilicon layer disposed on the first insulation layer;

a second insulation layer disposed on the first insulation layer and covering the polysilicon layer;

a gate metal layer disposed on the second insulation layer;

a third insulation layer disposed on the second insulation layer covering on the gate metal layer;

a first through hole and a second through hole located in the third insulation layer and the second insulation layer, wherein, the first through hole and the second through hole reveal a surface of the polysilicon layer;

a source metal layer and a drain metal layer disposed on the third insulation layer, wherein, the source metal

layer fills the first through hole and contacts with the surface of the polysilicon layer, and the drain metal layer fills the second through hole and contacts with the surface of the polysilicon layer;

a first planar layer disposed on the third insulation layer and covering the source metal layer and the drain metal layer;

a common electrode layer disposed on the first planar layer;

a first passivation layer disposed on the common electrode layer;

a via hole located in the first passivation layer, the common electrode layer and the first planar layer, wherein, the via hole reveals a surface of the drain metal layer;

a pixel electrode layer disposed on the first passivation layer, wherein, the pixel electrode layer is contacted with the surface of the drain metal layer by the via hole; and

a second passivation layer covering the pixel electrode layer.

12. The liquid crystal display panel according to claim 11, wherein, the color photoresist layer includes: a red photoresist layer, a green photoresist layer and a blue photoresist layer, wherein, the red photoresist layer, the green photoresist layer and the blue photoresist layer are disposed on the second passivation layer.

13. The liquid crystal display panel according to claim 12, wherein, the array substrate further includes: a second planar layer disposed on the color photoresist layer, wherein, the second planar layer fills the via hole.

14. The liquid crystal display panel according to claim 13, wherein, the multiple photo spacers includes: multiple main photo spacers and multiple sub photo spacers, wherein, the multiple main photo spacers and the multiple sub photo spacers are all located on the second planar layer.

15. The liquid crystal display panel according to claim 8, wherein, the liquid crystal display panel further includes: a black light-shielding layer disposed at a surface of the second substrate far away from the array substrate, wherein, the black light-shielding layer is disposed oppositely to the LTPS TFT, and a light-shielding area of the black light-shielding layer is greater than a light-shielding area of the light-shielding layer of the array substrate.

16. The liquid crystal display panel according to claim 9, wherein, the liquid crystal display panel further includes: a third passivation layer disposed at a surface of the second substrate far away from the array substrate and covering the black light-shielding layer.

* * * * *

专利名称(译)	液晶显示面板和相同的阵列基板		
公开(公告)号	US20170168347A1	公开(公告)日	2017-06-15
申请号	US14/889207	申请日	2015-08-12
[标]申请(专利权)人(译)	深圳市华星光电技术有限公司 武汉华星光电技术有限公司		
申请(专利权)人(译)	深圳市中国星光电科技有限公司. 中国武汉恒星光电科技有限公司.		
当前申请(专利权)人(译)	深圳市中国星光电科技有限公司 中国武汉恒星光电科技有限公司		
[标]发明人	LI YAFENG		
发明人	LI, YAFENG		
IPC分类号	G02F1/1335 G02F1/1343 G02F1/1339 G02F1/1362 G02F1/1368 G02F1/1333		
CPC分类号	G02F1/133512 G02F1/1368 G02F1/133345 G02F1/13394 G02F1/136227 G02F1/134309 G02F2202/104 G02F2201/121 G02F2001/136222 G02F2201/123 G02F2001/13396 G02F2201/40 G02F2001/13398 G02F1/136209		
优先权	201510413683.8 2015-07-14 CN		
其他公开文献	US10146078		
外部链接	Espacenet USPTO		

摘要(译)

公开了一种用于液晶显示面板的阵列基板。阵列基板包括第一基板，设置在第一基板上的低温多晶硅（LTPS）薄膜晶体管（TFT），设置在LTPS TFT上的彩色光刻胶层，以及设置在彩色光刻胶层上方的多个光间隔物。还公开了一种液晶显示面板，包括阵列基板和与阵列基板相对设置的第二基板。本发明利用第二基板与LTPS TFT阵列基板对准，以形成液晶显示板。因为第二衬底是裸衬底（没有图案），所以当第二衬底与阵列衬底对准时，不考虑对准精度。因此，液晶显示面板的孔径比没有差别。

